AMENDMENTS TO THE CLAIMS

Please amend the claims as indicated hereafter.

1. (Previously amended) A sacrificial composition of matter that decomposes to form airregions, the sacrificial composition comprising:

a sacrificial polymer that undergoes acid-catalyzed decomposition, wherein the sacrificial polymer is chosen from polypropylene carbonate (PPC), polyethylene carbonate (PEC), polycyclohexane carbonate (PCC), polycyclohexanepropylene carbonate (PCPC), polynorbornene carbonate (PNC), a copolymer of polynorbornene and polynorbornene carbonate, and combinations thereof; and

a catalytic amount of a photoacid generator, wherein the photoacid generator is chosen from a nucleophilic halogenide, a complex metal halide anion, and combinations thereof.

- 2. (Original) The composition of matter of claim 1, wherein the composition decomposes at a temperature range from about 100 to 120 °C.
- 3. (Original) The composition of matter of claim 1, wherein the composition decomposes at a temperature range from about 175 to 200 °C.
- 4. (Previously amended) The composition of matter of claim 1, wherein the composition decomposes at a temperature range from about 100 to 120 °C and leaves substantially no solid residue either from the polymer or the photoacid generator (PAG).

- 5. (Original) The composition of matter of claim 1, wherein the composition decomposes at a temperature range from about 100 to 120 °C after exposure to ultraviolet (UV) radiation.
- 6. (Original) The composition of matter of claim 1, wherein the composition acts as an adhesive.
- 7. (Original) The composition of matter of claim 1, wherein the composition is a positive tone sacrificial material.
- 8. 10. (Canceled)
- 11. (Original) The composition of matter of claim 1, wherein the photoacid generator is chosen from a diphenyliodononium salt, a triphenylsulfononium salt, a diphenylfluoronium salt, and combinations thereof.
- 12. (Previously Amended) The composition of matter of claim 1, wherein the photoacid generator is chosen from tetrakis(pentafluorophenyl)borate-4-methylphenyl[4-(1-methylethyl)phenyl] iodonium (DPI-TPFPB), tris(4-t-butylphenyl)sulfonium tetrakis-(pentafluorophenyl)borate (TTBPS-TPFPB), tris(4-t-butylphenyl)sulfonium hexafluorophosphate (TTBPS-HFP), triphenylsulfonium triflate (TPS-Tf), bis(4-tert-butylphenyl)iodonium triflate (DTBPI-Tf), triazine (TAZ-101), triphenylsulfonium hexafluoroantimonate (TPS-103), triphenylsulfonium bis(perfluoromethanesulfonyl) imide (TPS-N1), di-(p-t-butyl) phenyliodonium bis(perfluoromethanesulfonyl) imide (DTBPI-N1), triphenylsulfonium

tris(perfluoromethanesulfonyl) methide (TPS-C1), di-(p-t-butylphenyl) iodonium, tris(perfluoromethanesulfonyl)methide (DTBPI-C1), and combinations thereof.

13. (Original) The composition of claim 1, wherein the sacrificial polymer is about 1 to 50% by weight percent of the composition, and wherein the photoacid generator is from about 0.5 to 5% by weight of the composition.

14. – 31. (Cancelled)